Erratum to: Porous Structure Formation on Silicon Surface Treated by Plasma Focus Device

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The original version of this article unfortunately contained few mistakes.

1. The value of helium ion beam energy [3.035 MeV] in the text and in the caption of Fig. 7 was incorrect, and the correct value should read [3.7 MeV].

2. In Fig. 7a, the value of $E_0 = 1000$ keV was incorrect, and the correct value should be $E_0 = 3700$ keV.

The corrected Figure 7a is below

Fig. 7 RBS spectra of sample exposed to 1shot of PF at 1.5 cm distance using He beam at 3.7 MeV (a) and 1 MeV (b)

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